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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Zhang et al.  
Serial Number: 10/696,326  
Filed: October 29, 2003  
Group Art Unit: 1756  
Examiner: Unassigned  
Title: *Photomask Assembly and Method for  
Protecting the Same from Contaminants  
during a Lithography Process*

EV352394655US

**MAIL STOP - AMENDMENT**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

I hereby certify that this Information Disclosure Statement is being deposited with the United States Postal Service as Express Mail : EV352394655US addressed to: Mail Stop - Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on 11-1, 2004.

  
Angela Loding

**INFORMATION DISCLOSURE STATEMENT**

Applicants respectfully request, pursuant to 37 C.F.R. §§1.56, 1.97 and 1.98, that the references listed on the enclosed PTO-1449 form be considered and cited in the examination of the above-identified application. Applicants enclose a copy of the reference for the Examiner's convenience. Furthermore, pursuant to 37 C.F.R. §§1.97(g) and (h), no representation is made that this reference is material to the patentability of the present application.

Applicants believe no fees are due, however, the Commissioner is hereby authorized to charge any fees or credit any overpayments to Deposit Account No. 50-2148 of Baker Botts L.L.P.

Respectfully submitted,

BAKER BOTTS L.L.P.

Attorneys for Applicants

A handwritten signature in black ink, appearing to read "Paula D. Heyman", with a long horizontal flourish extending to the right.

Paula D. Heyman

Registration No. 48,363

AT CUSTOMER NO. **31625**  
512.322.2581  
512.322.8328(fax)

Date: Nov. 1, 2004

PTO-1449

NOV 01 2004

**Information Disclosure Citation  
in an Application**

Application No.

10/696,326

Applicant(s)

Zhang et al.

Docket Number

064441.0266

Group Art Unit

1756

Filing Date

10/29/2003

## U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
A.						
B.						
C.						
D.						
E.						
F.						
G.						
H.						
I.						
J.						
K.						
L.						
M.						
N.						
O.						

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
P.							
Q.							

## NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
R.	Kishkovich, Oleg, et al., "Airborne Molecular Contamination Control for DUV Lithography", Cleanroom Technology, vol. 6(5), pp. 31-33.	June 2000
S.		
T.		
U.		

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.